Date

: 8/8/2007

Patent No.

: 7,128,842 B1

Inventor(s)

: Zhang et al.

Issue Date

: October 31, 2006

Title

: POLYIMIDE AS A MASK IN VAPOR HYDROGEN FLUORIDE ETCHING

Doc./File No.

: 2269-7144.2US

Re: Certificate of Correction

Consideration has been given your request for a certificate of correction, for the above-identified patent under the provisions of Rule 1.322 and 1.323.

Respecting the alleged error(s) in the Assignee, inspection of the file of the application for the patent reveals that the Assignee (73), the data in box 3 of the issue fee transmittal, and on the Title page of the patent, is/are printed in accordance with the record in the Patent and Trademark Office, as passed to issued by the examiner. There being no fault on the part of the Patent and Trademark Office, it has no authority to issue a certificate of correction under the provision of 1.322. No correction is in order here.

In view of the foregoing, your request for certificate of correction is hereby denied.

However, further consideration will be given these matters, upon receipt of a request for certificate of correction under the provisions of 1:323, accompanied by the appropriate fee which is presently \$100.

Further consideration will be given, upon receipt of a renewed request or a request for reconsideration, which should be directed to:

Commissioner For Patents
P. O. BOX 1450
ALEXANDRIA, VA 22313-1450
Atten: Decisions & Certificates of Correction Branch

Ernest C. White, *LIE* (703) 308-9390 ext.#122 Cecelia B. Newman, *Supervisor* (703) 308-9390 ext. #101 Decisions & Certificates of Correction Branch

TRASK BRITT P.O. BOX 2550 SALT LAKE CITY UT 84110

ecw